

ABSTRACT

**CLEANING FLUID FOR SEMICONDUCTOR, AND CLEANING METHOD
USING THE SAME**

5 There is provided a cleaning fluid that effectively removes metal impurities and
the like existing on a portion through which a chemical solution for lithography passes,
before causing the chemical solution to pass through a semiconductor manufacturing
equipment in a lithography process, in order to prevent defects caused by the metal
impurities and the like found on a semiconductor substrate after forming a resist pattern
10 or after processing a semiconductor substrate in a process for manufacturing
semiconductor device. A cleaning fluid to clean a portion through which a chemical
solution for lithography passes in a semiconductor manufacturing equipment used in a
lithography process for manufacturing semiconductors, comprising: an inorganic acid;
water; and a hydrophilic organic solvent. In the cleaning fluid, the concentration of the
15 inorganic acid is preferably 0.0001% by mass to 60% by mass based on a total mass of
the cleaning fluid.

No suitable figure